FORM PTO-1449 (Modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)	ATTY. DOCKET NO. UMC-96-279 CON2	SERIAL NO. ~~Unassigned~~ 09/991,196
	APPLICANT Chih-Chien Liu , et al.	
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U.S. PATENT DOCUMENTS

EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	PATENTEE	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
RS		5,843,836	12/1998	Cheung, et al	438	626	
RS		5,851,899	12/1998	Weigand	438	427	
RS		5,858,869	1/1999	Chen, et al	438	597	
RS		5,885,894	3/1999	Wu, et al	438	624	
RS		5,913,140	6/1999	Roche, et al	438	624	
RS		6,117,345	9/2000	Liu, et al	216	19	

JC046 U.S. PTO 09/991196 11/20/01

FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION

		DOCUMENT NUMBER	PUBLISHED DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES	TRANSLATION NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

RS		J.T. Pye, et al., "*High-Density Plasma CVD and CMP for 0.25-μm Intermetal Dielectric Processing*," Solid State Technology, December 1995, pp. 65–69.

EXAMINER	Rabon Sergent	DATE CONSIDERED	6/23/03

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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